

### In the Specification

At page 1 before the "Technical Field" section, please insert the following:

#### --RELATED PATENT DATA

This patent resulted from a divisional application of U.S. Patent Application Serial No. 10/097,025, filed March 11, 2002, entitled "Atomic Layer Deposition Apparatus and Method", naming Trung Tri Doan and Gurtej S. Sandhu as inventor(s), the disclosure of which is incorporated by reference.--

Change the last starting paragraph on page 10 to read as follows:

Fig. 8 illustrates another alternate embodiment atomic layer deposition apparatus 10d. Like numerals from the above-described embodiments are utilized where appropriate, with differences being indicated with the suffix "d", or with different numerals. Atomic layer deposition apparatus 10d comprises a third non-roughing vacuum pump 60 in fluid communication with chamber 12d apart from substrate passageway 14. In one preferred embodiment, third non-roughing ~~vacuum pump 60~~ vacuum pump 60d is configured with chamber 12d for feeding a second deposition precursor to chamber 12d. For example, in one preferred embodiment, separate precursor feed pumps (i.e.,

~~pumps 26d and 60~~ pumps 26d and 60d) are separately optimized for their respective different deposition precursors (for example, in one or both of materials of construction or designed throughput) while another of the non-roughing vacuum pumps (i.e., pump 28d) is configured for feeding a purge gas to the chamber (for example, with respect to desired higher throughput than with the deposition precursors).

Change the complete paragraph on page 11 to read as follows:

The Fig. 8 depicted embodiment shows chamber 12d as being provided with ~~multiple outlets 32d, 34d and 62~~ multiple outlets 32d, 34d and 62d, which are in respective fluid communication with first non-roughing vacuum pump 26d, second non-roughing vacuum pump 28d and ~~third non-roughing vacuum pump 60~~ third non-roughing vacuum pump 60d, respectively. Fig. 9 depicts an alternate embodiment atomic layer deposition apparatus 10e wherein a chamber 12e is provided with one outlet 40e at the chamber. Outlet 40e is in fluid communication with each of first, second and third non-roughing vacuum pumps 32e, 34e and 60e, respectively. Of course, more than three non-roughing vacuum pumps could be utilized.